

# Wenshen Li

## List of Publications by Year in Descending Order

**Source:** <https://exaly.com/author-pdf/6870763/wenshen-li-publications-by-year.pdf>

**Version:** 2024-04-20

This document has been generated based on the publications and citations recorded by exaly.com. For the latest version of this publication list, visit the link given above.

The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

38  
papers

921  
citations

16  
h-index

30  
g-index

42  
ext. papers

1,197  
ext. citations

2.9  
avg, IF

4.55  
L-index

#	Paper	IF	Citations
38	Breakdown Mechanisms in $\text{AlGaIn}$ Trench-MOS Schottky-Barrier Diodes. <i>IEEE Transactions on Electron Devices</i> , <b>2022</b> , 69, 75-81	2.9	2
37	A unified thermionic and thermionic-field emission (TEFEE) model for ideal Schottky reverse-bias leakage current. <i>Journal of Applied Physics</i> , <b>2022</b> , 131, 015702	2.5	5
36	Gallium oxide power electronics. <i>APL Materials</i> , <b>2022</b> , 10, 029201	5.7	33
35	Distributed polarization-doped GaN p $\pi$ diodes with near-unity ideality factor and avalanche breakdown voltage of 1.25 kV. <i>Applied Physics Letters</i> , <b>2022</b> , 120, 122111	3.4	0
34	ON-Resistance of Ga $_{2\text{O}3}$ Trench-MOS Schottky Barrier Diodes: Role of Sidewall Interface Trapping. <i>IEEE Transactions on Electron Devices</i> , <b>2021</b> , 68, 2420-2426	2.9	5
33	Advanced concepts in Ga $_{2\text{O}3}$ power and RF devices. <i>Semiconductors and Semimetals</i> , <b>2021</b> , 107, 23-47	0.6	2
32	Thermal stability of epitaxial $\text{AlGaIn}$ and $(\text{Al,Ga})_{2\text{O}3}$ layers on m-plane sapphire. <i>Applied Physics Letters</i> , <b>2021</b> , 119, 062102	3.4	8
31	Thermal design of multi-fin Ga $_{2\text{O}3}$ vertical transistors. <i>Applied Physics Letters</i> , <b>2021</b> , 119, 103502	3.4	6
30	Near-ideal reverse leakage current and practical maximum electric field in $\text{AlGaIn}$ Schottky barrier diodes. <i>Applied Physics Letters</i> , <b>2020</b> , 116, 192101	3.4	42
29	. <i>IEEE Transactions on Electron Devices</i> , <b>2020</b> , 67, 3978-3982	2.9	1
28	GaN HEMTs on Si With Regrown Contacts and Cutoff/Maximum Oscillation Frequencies of 250/204 GHz. <i>IEEE Electron Device Letters</i> , <b>2020</b> , 41, 689-692	4.4	29
27	Field-Effect Transistors 5. <i>Springer Series in Materials Science</i> , <b>2020</b> , 639-660	0.9	
26	Degradation Mechanisms of GaN-Based Vertical Devices: A Review. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2020</b> , 217, 1900750	1.6	3
25	Field-Plated Ga $_{2\text{O}3}$ Trench Schottky Barrier Diodes With a BV $^2$ / $R_{\text{on}}$ of up to 0.95 GW/cm $^2$ . <i>IEEE Electron Device Letters</i> , <b>2020</b> , 41, 107-110	4.4	97
24	Guiding Principles for Trench Schottky Barrier Diodes Based on Ultrawide Bandgap Semiconductors: A Case Study in Ga $_{2\text{O}3}$ . <i>IEEE Transactions on Electron Devices</i> , <b>2020</b> , 67, 3938-3947	2.9	26
23	Thermionic emission or tunneling? The universal transition electric field for ideal Schottky reverse leakage current: A case study in $\text{AlGaIn}$ . <i>Applied Physics Letters</i> , <b>2020</b> , 117, 222104	3.4	14
22	Very High Parallel-Plane Surface Electric Field of 4.3 MV/cm in Ga $_{2\text{O}3}$ Schottky Barrier Diodes with PtOx Contacts <b>2020</b> ,		4

21	. <i>IEEE Transactions on Electron Devices</i> , <b>2020</b> , 67, 3954-3959	2.9	12
20	Realization of GaN PolarMOS using selective-area regrowth by MBE and its breakdown mechanisms. <i>Japanese Journal of Applied Physics</i> , <b>2019</b> , 58, SCCD15	1.4	12
19	Fin-channel orientation dependence of forward conduction in kV-class Ga <sub>2</sub> O <sub>3</sub> trench Schottky barrier diodes. <i>Applied Physics Express</i> , <b>2019</b> , 12, 061007	2.4	29
18	1.6 kV Vertical Ga <sub>2</sub> O <sub>3</sub> FinFETs With Source-Connected Field Plates and Normally-off Operation <b>2019</b> ,		19
17	. <i>IEEE Transactions on Electron Devices</i> , <b>2019</b> , 66, 4597-4603	2.9	8
16	Barrier Height Stability and Reverse Leakage Mechanisms in Ni/Ga <sub>2</sub> O <sub>3</sub> (001) Schottky Barrier Diodes <b>2019</b> ,		1
15	Field-plated Ga <sub>2</sub> O <sub>3</sub> Trench Schottky Barrier Diodes with a Record High Figure-of-merit of 0.78 GW/cm <sup>2</sup> <b>2019</b> ,		2
14	<b>2019</b> ,		23
13	Development of GaN Vertical Trench-MOSFET With MBE Regrown Channel. <i>IEEE Transactions on Electron Devices</i> , <b>2018</b> , 65, 2558-2564	2.9	32
12	Enhancement-Mode Ga <sub>2</sub> O <sub>3</sub> Vertical Transistors With Breakdown Voltage >1 kV. <i>IEEE Electron Device Letters</i> , <b>2018</b> , 39, 869-872	4.4	166
11	Activation of buried p-GaN in MOCVD-regrown vertical structures. <i>Applied Physics Letters</i> , <b>2018</b> , 113, 062105	3.4	25
10	<b>2018</b> ,		7
9	2.44 kV Ga <sub>2</sub> O <sub>3</sub> vertical trench Schottky barrier diodes with very low reverse leakage current <b>2018</b> ,		23
8	1230 V E-Ga <sub>2</sub> O <sub>3</sub> trench Schottky barrier diodes with an ultra-low leakage current of . <i>Applied Physics Letters</i> , <b>2018</b> , 113, 202101	3.4	61
7	Breakdown mechanism in 1 kA/cm <sup>2</sup> and 960 V E-mode E-Ga <sub>2</sub> O <sub>3</sub> vertical transistors. <i>Applied Physics Letters</i> , <b>2018</b> , 113, 122103	3.4	91
6	1.5 kV Vertical Ga <sub>2</sub> O <sub>3</sub> Trench-MIS Schottky Barrier Diodes <b>2018</b> ,		9
5	. <i>IEEE Transactions on Electron Devices</i> , <b>2017</b> , 64, 1635-1641	2.9	58
4	GaN vertical nanowire and fin power MISFETs <b>2017</b> ,		5

3	600 V GaN vertical V-trench MOSFET with MBE regrown channel <b>2017</b> ,	10
2	1.1-kV Vertical GaN p-n Diodes With p-GaN Regrown by Molecular Beam Epitaxy. <i>IEEE Electron Device Letters</i> , <b>2017</b> , 38, 1071-1074	4-4 50
1	Photoelectric Generation Coefficient of B-Gallium Oxide during Exposure to High-Energy Ionizing Radiation. <i>Physica Status Solidi (A) Applications and Materials Science</i> ,2100700	1.6